

Taiwan National Nano Devices Laboratories (NDL) Producing Sub-25 nm Trenches Using Nanonex Nanoimprint Solution

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Princeton, New Jersey, July 15, 2004, Nanonex Co., the leading provider in nanoimprint solution, announced that Taiwan National Nano Devices Laboratories (NDL) has produced sub-25 nm trenches using Nanonex Nanoimprint Solution, that consists of Nanonex's imprinter (NX-1000), resists, and masks.